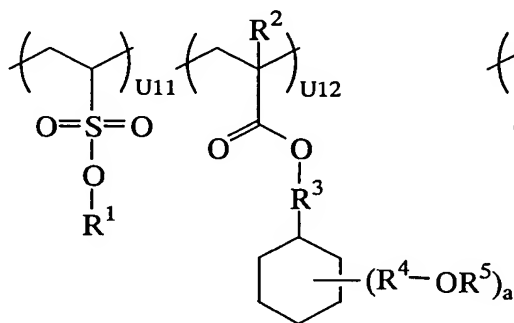
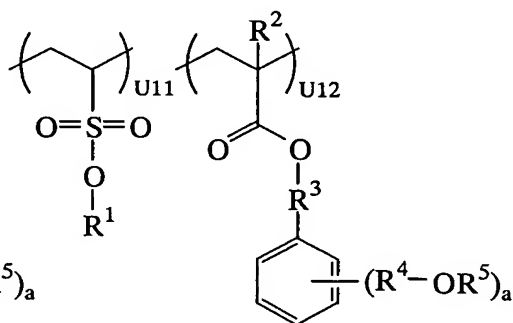


ABSTRACT

A polymer comprising recurring units of (1a) or (1b)
5 wherein R^1 is an acid labile group, adhesive group or
fluoroalkyl, R^2 is H, F, alkyl or fluoroalkyl, R^3 and R^4 each
are a single bond, alkylene or fluoroalkylene, R^5 is H or an
acid labile group, "a" is 1 or 2, $0 < U_{11} < 1$ and $0 < U_{12} < 1$
and having a Mw of 1,000-500,000 is used as a base resin to
10 formulate a resist composition which is sensitive to
high-energy radiation, maintains high transparency at a
wavelength of up to 200 nm, and has improved alkali
dissolution contrast and plasma etching resistance.



(1a)



(1b)